

Electronic supplementary information (ESI†)

Ultra-sensitive photoluminescence modification of Eu³⁺ ion based on light tuning surface potential of Bi₃O₄Cl layered semiconductor and application for facile UV light detector

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Table S1. Rietveld Refinement and Lattice Parameters of Bi₃O₄Cl and Bi₃O₄Cl:5%Eu³⁺

	Bi ₃ O ₄ Cl	Bi ₃ O ₄ Cl:5%Eu ³⁺
space group	<i>I</i> ₂ / <i>a</i> ¹ (15)	<i>I</i> ₂ / <i>a</i> ¹ (15)
<i>a</i> (Å)	5.695	5.683
<i>b</i> (Å)	5.648	5.636
<i>c</i> (Å)	18.573	18.541
β (deg)	91.52	91.35
Z	4	4
<i>V</i> (Å ³)	597.20	593.75

According to the Rietveld refined results, the as-prepared Bi₃O₄Cl:Eu³⁺ phosphor is assigned to the monoclinic system and belongs to the *I*₂/*a*¹(15) space group. The lattice parameters are confirmed as *a* = 5.683 Å, *b* = 5.636 Å, *c* = 18.541 Å, β = 91.52°, *Z* = 4, and *V* = 593.75 Å³.^{1,2} Compared with the standard cell parameters and cell volume that derive from PDF#86-2221, all values of Bi₃O₄Cl:Eu³⁺ sample show a significant shrinkage, proving the vast substitution of Eu³⁺ ions (1.066 Å, CN = 8) for the bigger Bi³⁺ sites (1.17 Å, CN = 8).

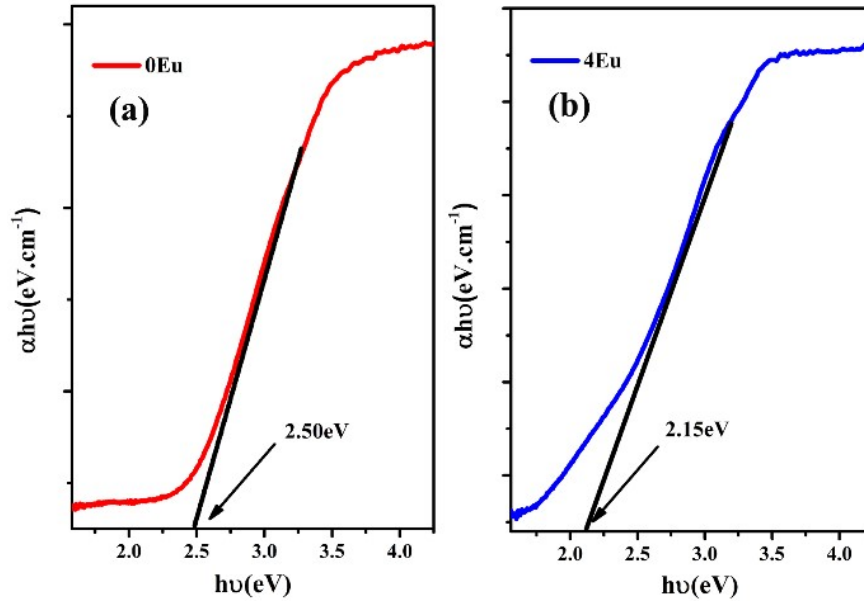


Fig. S1. Plots of $(\alpha hv)^{1/2}$ vs. the photon energy ($h\nu$) for the as-synthesized undoped $\text{Bi}_3\text{O}_4\text{Cl}$ sample (a) and the $\text{Bi}_3\text{O}_4\text{Cl}:4\%\text{Eu}^{3+}$ sample (b).

As showed in **Fig. S1a-b**, the absorption edge of Eu^{3+} doped $\text{Bi}_3\text{O}_4\text{Cl}$ sample slightly redshifts compared with that of undoped one (for simplifying, just represented the representative curves of sample with 0 and 4 mol% Eu^{3+}). It indicates that Eu^{3+} ion dopant forming impurity energy levels decreases the forbidden gap of $\text{Bi}_3\text{O}_4\text{Cl}$, and the calculation of energy band structure is being done by our group.²

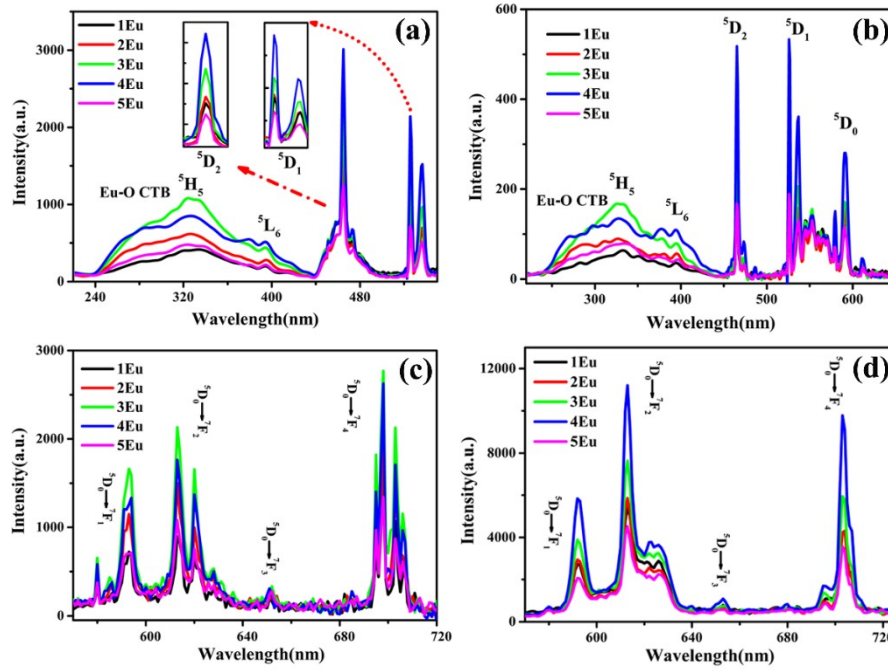


Fig. S2. (a)-(b) Excitation spectra of $\text{Bi}_3\text{O}_4\text{Cl}:x\text{Eu}^{3+}$ ($x = 1, 2, 3, 4,$ and 5 mol%) microrystals recorded at $\lambda_{\text{Em}} = 613$ nm and 704 nm; (c)-(d) Emission spectra of the same samples upon 320 nm and 465 nm excitation. The insets are the enlarged excitation spectra in ${}^7\text{F}_0 \rightarrow {}^5\text{D}_2$ and ${}^7\text{F}_0 \rightarrow {}^5\text{D}_1$ transition region, and other excitation bands followed the similar tendency but without presentation for simplifying.

Fig. S2 presents the excitation spectra (a-b) and emission spectra (c-d) of prepared Eu^{3+} doped $\text{Bi}_3\text{O}_4\text{Cl}$ samples with different concentration of Eu^{3+} ions. It shows that whether under absorption-edge (394 and 465 nm) or intraband (526 nm) excitation, the concentration dependence of the emission intensity of Eu^{3+} ion are totally same, except that under deep-UV excitation (320 nm) (Figure S3c-d). This indicates that the photoexcited electrons from broadband excitation may be excited via intermediate electron-hole pair states of semiconductor.

As for the decay times of Eu^{3+} -related emission for $\text{Bi}_3\text{O}_4\text{Cl}:4\%\text{Eu}^{3+}$ sample, all decay profiles keep following the single exponential decay equation: $I = A\exp(-t/\tau)$,^{3,4} where parameters A , I , and t are represent the constant, luminescent intensity, and the decay time,

respectively. Therefore, under 465 nm excitation, the lifetimes of sample were calculated to 1.00 ms ($\lambda_{Em} = 613$ nm), 0.92 ms ($\lambda_{Em} = 620$ nm), 0.91 ms ($\lambda_{Em} = 698$ nm), and 0.99 ms ($\lambda_{Em} = 704$ nm), respectively. Meanwhile, under 320 nm irradiation, the obtained results are 1.24 ms ($\lambda_{Em} = 613$ nm), 1.17 ms ($\lambda_{Em} = 620$ nm), 1.15 ms ($\lambda_{Em} = 698$ nm), and 1.17 ms ($\lambda_{Em} = 704$ nm), respectively.

Reference

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